

## REFERENCE LIST

SEMICONDUCTOR  
SOLAR  
PHARMA  
POWER GENERATION  
FOOD & BEVERAGE  
PULP AND PAPER  
CHEMICAL  
OIL AND GAS  
MINING  
AEROSPACE AND TRANSPORT  
**STANDARD EQUIPMENT**



# Functional Water Systems



The following list gives some information about just a selection of the many hundreds of Functional Water units that have been supplied to a very wide variety of clients throughout the electronics industry, worldwide.

Unfortunately, due to the secrecy agreements in place with most of our clients, we are unable to disclose our client's names, their factory locations, or much information about the applications they are used for. We take the confidences of all our clients very seriously and hope that you will understand this. However, we hope that the list below will demonstrate clearly that we have a great deal of experience in the production of both oxidising and reducing ultrapure water for use in a variety of applications within the electronics industry.

If you would like to receive further selected information about any of the following applications, or further information about the use and applications of Functional Water units, please do contact us at the above address and we will be pleased to provide additional information.



**Model G-2400**



**Model H-300**

In the following list, the various types of Functional Water units supplied are as listed below:

Type I: Electrolytic Ionised water, Type II: Gas Dissolved Water ( $H_2 + O_3$ )

H: Hydrogen Water, O: Ozone water, OR: Water degasser unit, NH: Ammonia

Type	Flow Rate (l/h)	Objective	Note
I	400	LSI manufacture	CMP/Wafer cleaning
I	400	LCD manufacture	TFT process
I	100	LCD manufacture	TFT process
I	100	Wafer manufacture	Post polish cleaning /Wafer cleaning
I	100	LSI manufacture	RCA cleaning
I	100	Equipment manufacturer	wet scrubber
I	100	Wafer manufacture	Post polish cleaning /Wafer cleaning
I	1080	LCD manufacture	LCD process
II	1200 / 2400 /3600	LCD manufacture	LCD process
I	1200	LSI manufacture	CMP
I	1200	Equipment manufacturer	Wet scrubber/Wafer cleaning
I	600		
II	O <sub>3</sub> 180 / H <sub>2</sub> 300	LCD manufacture	TFT process
I	2400	LCD manufacture	TFT process
H	48000	LCD manufacture	TFT process
H	2400	LCD manufacture	Cell process cleaning
II	O <sub>3</sub> 600 / H <sub>2</sub> 1200	Wafer manufacture	Post polish cleaning /Wafer cleaning
II	O <sub>3</sub> 600 / H <sub>2</sub> 2400	Wafer manufacture	Post polish cleaning /Wafer cleaning
I	200	Equipment manufacturer	CMP
I	200	Wafer manufacture (RTD)	Post polish cleaning /Wafer cleaning
II	O <sub>3</sub> 1200 / H <sub>2</sub> 4200	Wafer manufacture	Post polish cleaning /Wafer cleaning
H	2400	LSI manufacture	Wafer cleaning
II	O <sub>3</sub> 600 / H <sub>2</sub> 1200		
II	O <sub>3</sub> 300 / H <sub>2</sub> 4200	Wafer manufacture	Post polish cleaning /Wafer cleaning
H	2400		
H	300	Equipment manufacturer	
H		LCD manufacture	TFT process
I		LCD manufacture	TFT process
I	60	R&D	Analysis equipment cleaning
H		LCD manufacture	TFT process
II		LSI manufacture	Post polish cleaning /Wafer cleaning

Type	Flow Rate (l/h)	Objective	Note
II	O <sub>3</sub> 1200 / H <sub>2</sub> 1200	Lens manufacture	Post polish cleaning
H	900	LSI manufacture	Final cleaning
H	900	LSI manufacture	Final cleaning
H	900	LSI manufacture	CMP
H	900	Mask manufacture	Mask cleaning
H	2400	HD manufacture	HD cleaning
H	2400	Mask manufacture	Mask cleaning
H	900	Mask manufacture	Mask cleaning
I	600	Equipment manufacturer	Mask cleaning
H	900	LSI manufacture	CMP
O	1200	Wafer manufacture	Final cleaning
O	1200	Wafer manufacture	Final cleaning
O	1200	Wafer manufacture	Final cleaning
O	1200	Wafer manufacture	Final cleaning
O	1200	Wafer manufacture	Final cleaning
O	1200	Wafer manufacture	Final cleaning
O	1200	Wafer manufacture	Final cleaning
H	900	R&D	R&D
H	2400	Mask manufacture	Mask cleaning
H	900	LSI manufacture	CMP
H	900	Equipment manufacturer	CMP
H	1200	Mask manufacture	Mask cleaning
H	1200	Mask manufacture	Mask cleaning
H	900	Equipment manufacturer	R&D
I	600	Equipment manufacturer	R&D
H	900	Equipment manufacturer	Cleaning machine
H	1200	Mask manufacture	Mask cleaning
O	1200	Wafer manufacture	Final cleaning
O	1200	Wafer manufacture	Final cleaning
H	2400	R&D	R&D
H	2400	R&D	R&D

Type	Flow Rate (l/h)	Objective	Note
II	O <sub>3</sub> 600 / H <sub>2</sub> 600	Wafer manufacture	Final cleaning
II	O <sub>3</sub> 600 / H <sub>2</sub> 1200	Lens manufacture	Post polish cleaning
I	200	Equipment manufacturer	Cleaning machine
H	2400	Wafer manufacture	Mask cleaning
H	7200	LCD manufacture	Glass cleaning
H	900	Equipment manufacturer	Cleaning machine
H	900	Equipment manufacturer	Cleaning machine
H	900	Equipment manufacturer	Cleaning machine
H	900	Equipment manufacturer	Cleaning machine
H	900	Equipment manufacturer	Cleaning machine
H	900	Equipment manufacturer	Cleaning machine
H	900	Equipment manufacturer	Cleaning machine
H	900	Equipment manufacturer	Cleaning machine
H	900	Equipment manufacturer	Cleaning machine
H	1200	Equipment manufacturer	Cleaning machine
H	2400	Equipment manufacturer	Cleaning machine
H	2400	LSI manufacture	CMP
H	2400	R&D	R&D
II	O <sub>3</sub> 600 / H <sub>2</sub> 1200		
H	900	Equipment manufacturer	Cleaning machine
H	900	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
H	1200	LSI manufacture	CMP
H	1200	LSI manufacture	CMP
II	O <sub>3</sub> 1200 / H <sub>2</sub> 1200		Glass cleaning
OR	2400	Equipment manufacturer	Cleaning machine
H	900	Equipment manufacturer	Mask cleaning
H	900	Equipment manufacturer	Mask cleaning
H	1200	LSI manufacture	CMP
H	1200	LSI manufacture	CMP

Type	Flow Rate (l/h)	Objective	Note
H	1200	LSI manufacture	CMP
H	1200	LSI manufacture	CMP
H	1200	LSI manufacture	CMP
H	1200	LSI manufacture	CMP
H	1200	LSI manufacture	CMP
H	1200	LSI manufacture	CMP
H	1200	LSI manufacture	CMP
H	1200	LSI manufacture	CMP
II	O <sub>3</sub> 1200 / H <sub>2</sub> 1200		
OR	1500		R&D
H	1200	LSI manufacture	CMP
H	1200	LSI manufacture	CMP
H	1200	LSI manufacture	CMP
H	1200	LSI manufacture	CMP
H	3600	Glass manufacture	
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
H	300		R&D
H	900	LSI manufacture	BEOL
H	1200	LSI manufacture	CMP
H	900	Equipment manufacturer	Cleaning machine
H	300	Equipment manufacturer	Cleaning machine
H	120	Equipment manufacturer	Cleaning machine
H	2400	LSI manufacture	CMP
H	2400	LSI manufacture	CMP
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine

Type	Flow Rate (l/h)	Objective	Note
OR	2400	Equipment manufacturer	Cleaning machine
H	300	Equipment manufacturer	Cleaning machine
H	300		
H	900	LCD manufacture	Glass cleaning
OR	2400	Equipment manufacturer	Cleaning machine
O	1200	Mask manufacture	Mask cleaning
H	300	Equipment manufacturer	Cleaning machine
O	120	Equipment manufacturer	Cleaning machine
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
OR	2500	Wafer manufacture	Wafer cleaning
H	900	LSI manufacture	CMP
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	270	LSI manufacture	
OR		Equipment manufacturer	Cleaning machine
H	300	Equipment manufacturer	Cleaning machine
H	2400	LSI manufacture	CMP
H	300		
OR		Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine
OR	2400	Equipment manufacturer	Cleaning machine

Type	Flow Rate (l/h)	Objective	Note
O	2000	LCD manufacture	
H	1200	LCD manufacture	
O	120	Equipment manufacturer	Cleaning machine
H	300	Equipment manufacturer	Cleaning machine
O	2400	LCD manufacture	
H	2400	LCD manufacture	
NH	2400	Component cleaning	Tool supplier for new process
NH	2400	Component cleaning	Tool supplier for new process
NH	2400	Component cleaning	Tool supplier for new process
NH	2400	Component cleaning	Tool supplier for new process
NH	2400	Component cleaning	Tool supplier for new process



H+E ranks among the world's leading suppliers in the fields of: water & wastewater treatment, and energy efficiency. Based on its global presence, the **H+E GROUP** has completed projects in over 50 countries.



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